	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	1027	703/13.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:45
2	BRS	L3	9	(granik-y).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:47
3	BRS	L4	1	(granik-y).in. and (distortion$3)"."	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:47
4	BRS	L5	0	(granik-y).in. and (distortion$3).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:48
5	BRS	L6	0	(granik-y).in. and (mask).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:48

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L7	0	(granik-y).in. and (etch).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:48
7	BRS	L8	0	(granik-y).in. and (optic$3).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:48
8	BRS	L9	5	(schellenberg-f).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:49
9	BRS	L11	0	(metor-graphics-corporation).as.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:49
10	BRS	L14	71	(mentor-graphics-corporation).as. and optical	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:50

	Type	L #	Hits	Search Text	DBs	Time Stamp
11	BRS	L16	14	(mentor-graphics-corporation).as. and optical and etch and mask	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:50
12	BRS	L15	1	(mentor-graphics-corporation).as. and optical and etch and mack	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:50
13	BRS	L12	151	(mentor-graphics-corporation).as.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:53
14	BRS	L17	4172	(mask same reticle same litho$9)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:54
15	BRS	L18	76	(mask same reticle same litho$9 same distortions)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:58

	Type	L #	Hits	Search Text	DBs	Time Stamp
16	BRS	L19	16	(mask same reticle same litho$9 same distortions) and (read same data)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 13:59
17	BRS	L20	2	(mask same reticle same litho$9 same distortions) and (read same data) and (simulation same etch)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:01
18	BRS	L21	23	(simul$6 same etch same mask same reticle)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:02
19	BRS	L22	25545	(optical adj process adj correction) or (OPC)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:03
20	BRS	L23	801	((optical adj process adj correction) or (OPC)) same (simula$6)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:03

	Type	L #	Hits	Search Text	DBs	Time Stamp
21	BRS	L24	195	((optical adj process adj correction) or (OPC)) same (simula$6) and (etch$3 same simula$6)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:04
22	BRS	L25	33	((optical adj process adj correction) or (OPC)) same (simula$6) and (etch$3 same simula$6 same distor$6)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:05
23	BRS	L26	32	((optical adj process adj correction) or (OPC)) same (simula$6) and (etch$3 same simula$6 same distor$6) and wafer	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:07
24	BRS	L27	25	((optical adj process adj correction) or (OPC)) same (simula$6) and (etch$3 same simula$6 same distor$6) and wafer and (compen$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 15:29
25	BRS	L28	0	((optical adj process adj correction) or (OPC)) same (simula$6) and (etch$3 same simula$6 same distor$6) and wafer and (compen$5) and (mask and recticle)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:07

	Type	L #	Hits	Search Text	DBs	Time Stamp
26	BRS	L29	0	((optical adj process adj correction) or (OPC)) same (simula$6) and (etch$3 same simula$6 same distor$6) and wafer and (compen$5) and (read and write)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 15:35
27	BRS	L30	4	"09747190"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:15
28	BRS	L31	690	("09747190") and simulation and etch and distortions (OPC) and wafer and compensate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:16
29	BRS	L32	690	("9747190") and simulation and etch and distortions (OPC) and wafer and compensate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:16
30	BRS	L33	690	"7017141".pn. and simulation and etch and distortions (OPC) and wafer and compensate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 14:17
31	BRS	L34	314	"7017141".pn. and simulation and etch and distortions (OPC) and wafer and compensate	USPAT	2007/02/02 14:17

	Type	L #	Hits	Search Text	DBs	Time Stamp
32	BRS	L35	1	"7017141".pn. and simulation and etch and distortions and (OPC) and wafer and compensate	USPAT	2007/02/02 14:18
33	BRS	L36	1	"7017141".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read	USPAT	2007/02/02 14:18
34	BRS	L37	0	"7017141".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and write	USPAT	2007/02/02 14:18
35	BRS	L38	1	"7017141".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and (writ$6)	USPAT	2007/02/02 14:19
36	BRS	L39	1	"7017141".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and (writ$6) and reticle	USPAT	2007/02/02 14:19
37	BRS	L40	1	"7017141".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and (writ$6) and reticle and mask	USPAT	2007/02/02 14:20
38	BRS	L41	1	"7017141".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and (writ$6) and reticle and mask and (rule$3)	USPAT	2007/02/02 14:20
39	BRS	L42	0	"7017141".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and (writ$6) and reticle and mask and (rule$3) and table	USPAT	2007/02/02 14:20
40	BRS	L43	1	"7017141".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and (writ$6) and reticle and mask and (rule$3)	USPAT	2007/02/02 14:23
41	BRS	L44	0	"6425113".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and (writ$6) and reticle and mask and (rule$3)	USPAT	2007/02/02 14:24
42	BRS	L45	1	"6415421".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and (writ$6) and reticle and mask and (rule$3)	USPAT	2007/02/02 14:47
43	BRS	L46	1	"6415421".pn. and simulation and etch and distortions and (OPC) and wafer and compensate and read and (writ$6) and reticle and mask and (rule$3) and lith$9	USPAT	2007/02/02 15:29
44	BRS	L47	0	"6415421".pn. and bias	USPAT	2007/02/02 15:29

	Type	L #	Hits	Search Text	DBs	Time Stamp
45	BRS	L48	3	((optical adj process adj correction) or (OPC)) same (simula$6) and (etch$3 same simula$6 same distor$6) and wafer and (compen$5) and bias	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 15:30
46	BRS	L49	3	((optical adj process adj correction) or (OPC)) same (simula$6) and (etch$3 same simula$6 same distor$6) and bias	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 15:31
47	BRS	L50	7295	(etch same bias)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 15:38
48	BRS	L51	3	(etch same bias same reticle same distortion)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 15:39
49	BRS	L52	38	(etch same bias) and (reticle same distortion)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 15:39

	Type	L #	Hits	Search Text	DBs	Time Stamp
50	BRS	L53	36	(etch same bias) and (reticle same distortion) and mask and reticle	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 15:40
51	BRS	L54	14	(etch same bias) and (reticle same distortion) and mask and reticle and simulation	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 15:44
52	BRS	L55	1022	716/21.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 16:21
53	BRS	L56	180	716/21.ccls. and bias	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 16:22
54	BRS	L57	72	716/21.ccls. and bias and etch	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 16:23

	Type	L #	Hits	Search Text	DBs	Time Stamp
55	BRS	L58	50	716/21.ccls. and bias and etch and simulation	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 16:23
56	BRS	L59	54	716/21.ccls. and bias and etch and simul$6	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 16:23
57	BRS	L60	14	716/21.ccls. and (bias same etch) and simul$6	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	2007/02/02 16:23

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4	INZZ	3 AND simulation	unrestricted	217	show titles
5	INZZ	4 AND wafer	unrestricted	36	show titles
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